

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|------------------|
| L1 | 5882 | ((438/378) or (438/402) or (438/407) or (438/423) or (438/455) or (438/471) or (438/476) or (438/514) or (438/517) or (438/520) or (438/528) or (438/530) or (438/795) or (438/798) or (438/918) or (438/967)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/01/12 18:27 |
| L2 | 27 | 1 and (flash near5 anneal\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/12 18:37 |
| L3 | 6780 | ((438/149) or (438/311) or (438/458) or (438/473) or (438/474) or (438/475) or (438/477) or (438/479) or (438/480) or (438/495) or (438/496) or (438/499) or (438/406) or (438/508) or (438/509) or (438/514) or (438/787) or (438/788)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/01/12 18:33 |
| L4 | 19 | 3 and (flash near5 anneal\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/12 18:37 |
| L5 | 9 | 4 not "27" | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/12 18:37 |
| L6 | 14 | 4 not 2 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/12 18:37 |
| S1 | 6192 | ((438/149) or (438/311) or (438/458) or (438/473) or (438/474) or (438/475) or (438/477) or (438/479) or (438/480) or (438/495) or (438/496) or (438/499) or (438/406) or (438/508) or (438/509) or (438/514) or (438/787) or (438/788)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/01/12 18:33 |

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| S2 | 17530 | (soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/12 18:28 |
| S3 | 0 | ((((xe adj arc) near2 lamp) same anneal\$3) near10 ((support or second silicon or quartz or semiconductor)near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:48 |
| S4 | 0 | ((((xe adj arc) near2 lamp) same anneal\$3) same ((support or second silicon or quartz or semiconductor)near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:48 |
| S5 | 0 | ((((xe adj arc) near2 lamp) same anneal\$3) same ((support or second or silicon or quartz or semiconductor)near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:49 |
| S6 | 0 | ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (((xe adj arc) near2 lamp) same anneal\$3) and ((support or second or silicon or quartz or semiconductor)near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:49 |
| S7 | 26 | ((((xe adj arc) near2 lamp) same anneal\$3) and ((support or second or silicon or quartz or semiconductor)near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:50 |
| S8 | 5 | ((((xe adj arc) near2 lamp) same (anneal\$3 or heat\$3)) near10 (substrate or (support near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:52 |
| S9 | 54 | ((((xe adj arc) near2 lamp) same (anneal\$3 or heat\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:53 |
| S10 | 0 | ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (((xe adj arc) near2 lamp) same (anneal\$3 or heat\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:53 |

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| S11 | 206 | ((((xe adj arc) near2 lamp) and (anneal\$3 or heat\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:03 |
| S12 | 0 | (((((xe adj arc) near2 lamp) and (anneal\$3 or heat\$3))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) and (((438/149) or (438/311) or (438/458) or (438/473) or (438/474) or (438/475) or (438/477) or (438/479) or (438/480) or (438/495) or (438/496) or (438/499) or (438/406) or (438/508) or (438/509) or (438/514) or (438/787) or (438/788)).CCLS:) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:53 |
| S13 | 34 | (((((xe adj arc) near2 lamp) and (anneal\$3 or heat\$3))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 17:53 |
| S14 | 10693 | wafer near2 bond\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:19 |
| S15 | 2450 | ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (wafer near2 bond\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:02 |
| S16 | 0 | ((((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (wafer near2 bond\$3)) and (((xe adj arc) near2 lamp) and (anneal\$3 or heat\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:02 |
| S17 | 3933068 | anneal\$3 or heat\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:55 |

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| S18 | 1808 | (anneal\$3 or heat\$3) and (((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (wafer near2 bond\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:05 |
| S19 | 281 | ((xe adj arc) near2 lamp) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:03 |
| S20 | 0 | ((anneal\$3 or heat\$3) and (((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (wafer near2 bond\$3))) and (((xe adj arc) near2 lamp)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:04 |
| S21 | 40 | ((anneal\$3 or heat\$3) and (((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) and (wafer near2 bond\$3))) and (lamp near5 intensit\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:29 |
| S22 | 15436 | wafer near5 bond\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:20 |
| S23 | 8537 | (wafer near5 bond\$3) and (anneal\$3 or heat\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:20 |
| S24 | 1232 | implant\$ near5 (hydrogen near ion\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:27 |
| S25 | 179 | (wafer near5 bond\$3) same (implant\$ near5 (hydrogen near ion\$1)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:57 |
| S26 | 162 | ((wafer near5 bond\$3) same (implant\$ near5 (hydrogen near ion\$1))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:28 |

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| S27 | 158 | ((((wafer near5 bond\$3) same (implant\$ near5 (hydrogen near ion\$1))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) and (anneal\$3 or heat\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:28 |
| S28 | 2 | (((((wafer near5 bond\$3) same (implant\$ near5 (hydrogen near ion\$1))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) and (anneal\$3 or heat\$3)) and (lamp near5 intensit\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:38 |
| S29 | 37 | (((((wafer near5 bond\$3) same (implant\$ near5 (hydrogen near ion\$1))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) and (anneal\$3 or heat\$3)) and lamp | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:31 |
| S30 | 366 | ((wafer near5 bond\$3) and (implant\$ near5 (hydrogen near ion\$1))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:58 |
| S31 | 310 | ((wafer near5 bond\$3) and (implant\$ near5 (hydrogen near ion\$1))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:58 |
| S32 | 0 | (((((wafer near5 bond\$3) and (implant\$ near5 (hydrogen near ion\$1))) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) and (((anneal\$3 or heat\$3) same lamp) near5 (support near2 substrate))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:59 |
| S33 | 0 | ((wafer near5 bond\$3) and (implant\$ near5 (hydrogen near ion\$1))) and (((anneal\$3 or heat\$3) same lamp) near5 (support near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:59 |

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| S34 | 0 | ((anneal\$3 or heat\$3) same lamp) near5 (support near2 substrate)) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 18:59 |
| S35 | 43 | ((anneal\$3 or heat\$3) same lamp) near5 (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:01 |
| S36 | 2013 | (anneal\$3 or heat\$3) near3 (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:02 |
| S37 | 71 | ((anneal\$3 or heat\$3) near3 (support near2 substrate)) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:02 |
| S38 | 16 | ((anneal\$3 or heat\$3) near3 (support near2 substrate)) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer))) and (implant\$ near5 (hydrogen near ion\$1)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:03 |
| S39 | 1 | "5543636".PN. | USPAT | OR | OFF | 2004/08/20 19:22 |
| S40 | 4 | ("5854123" "5882987" "5953622" "6010579").PN. | USPAT | OR | OFF | 2004/08/20 19:23 |
| S41 | 6 | ("5374564" "5882987" "6146979" "6251754" "6294814" "6323108").PN. | USPAT | OR | OFF | 2004/08/20 19:24 |
| S42 | 1 | ("6376806").PN. | USPAT; USOCR | OR | OFF | 2004/08/20 19:35 |
| S43 | 15 | ("4356384" "4436985" "4707217" "4755654" "5073698" "5577157" "5722761" "5756369" "5811327" "5840118" "5892332" "5893952" "5937282" "6080965" "6144171").PN. | USPAT | OR | OFF | 2004/08/20 19:36 |

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| S44 | 335 | flash near2 anneal\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:52 |
| S45 | 0 | (flash near2 anneal\$3) near5 (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:40 |
| S46 | 1 | (flash near2 anneal\$3) near10 (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:40 |
| S47 | 1 | (flash near2 anneal\$3) same (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:40 |
| S48 | 7 | (flash near2 anneal\$3) and (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:44 |
| S49 | 0 | (flash near2 anneal\$3) near5 (separt\$5 same substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:45 |
| S50 | 0 | (flash near2 anneal\$3) near5 separt\$5 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:45 |
| S51 | 0 | (flash near2 anneal\$3) near10 separt\$5 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:46 |
| S52 | 2 | (flash near2 anneal\$3) near10 (through near5 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:47 |
| S53 | 1 | (flash near2 anneal\$3) near10 (through near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:48 |

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| S54 | 1 | (flash near2 anneal\$3) near10 (through same substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:48 |
| S55 | 27 | (flash near2 anneal\$3) near10 (substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:50 |
| S56 | 1 | (flash near2 anneal\$3) same (hydrogen near2 ion\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:29 |
| S57 | 18 | flash near2 anneal\$3 and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:55 |
| S58 | 42016 | flash near2 anneal\$3 or ((xe adj arc) near2 lamp) or xenon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 18:41 |
| S59 | 20 | (flash near2 anneal\$3 or ((xe adj arc) near2 lamp) or xenon) same ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) near3 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/20 19:56 |
| S60 | 41728 | ((xe adj arc) near2 lamp) or xenon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:30 |
| S61 | 40914 | (soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:28 |
| S62 | 869 | (((xe adj arc) near2 lamp) or xenon) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:28 |
| S63 | 1422 | (hydrogen near2 ion\$1) near5 implant\$5 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:29 |

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| S64 | 47 | ((((xe adj arc) near2 lamp) or xenon) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)))) and ((hydrogen near2 ion\$1) near5 implant\$5) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:29 |
| S65 | 19527 | ((xe adj arc) near2 lamp) or xenon near3 lamp | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:30 |
| S66 | 330 | (((xe adj arc) near2 lamp) or xenon near3 lamp) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:30 |
| S67 | 13 | ((((xe adj arc) near2 lamp) or xenon near3 lamp) and ((soi or (silicon near2 insulator) or soq or (silicon near2 quartz) or sof or (silicon near2 foreign)))) and ((hydrogen near2 ion\$1) near5 implant\$5) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 16:31 |
| S68 | 35 | (flash near2 anneal\$3) near5 (substrate or wafer) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/04 17:25 |
| S69 | 0 | (flash near2 anneal\$3) near10 ((back or bottom) near5 (substrate or wafer)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 20:54 |
| S70 | 0 | (flash near2 anneal\$3) near10 (imping\$3 near5 (support near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 21:31 |
| S71 | 0 | anneal\$3 near10 (imping\$3 near5 (support near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 21:32 |
| S72 | 0 | anneal\$3 same (imping\$3 near5 (support near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 21:32 |

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| S73 | 0 | anneal\$3 same (imping\$3 or though) near5 (support near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 21:33 |
| S74 | 10 | anneal\$3 same ((imping\$3 or through) near5 (support near2 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 21:35 |
| S75 | 8 | (flash near2 anneal\$3 same ((imping\$3 or through) near5 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/21 21:35 |
| S76 | 6752 | ((438/149) or (438/311) or (438/458) or (438/473) or (438/474) or (438/475) or (438/477) or (438/479) or (438/480) or (438/495) or (438/496) or (438/499) or (438/406) or (438/508) or (438/509) or (438/514) or (438/787) or (438/788)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/01/04 17:23 |
| S77 | 0 | S76 and (flash near5 anneal\$3) near5 ((quartz or glass) near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/04 17:27 |
| S78 | 2 | (flash near5 anneal\$3) near5 ((quartz or glass) near2 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/01/04 17:27 |